



## Special Issue: Ion Implantation Technology

**Submission Deadline: September 23, 2022**

This special issue of *MRS Advances* focusses on discussion of major challenges in current and emerging technologies related to implant/doping and annealing processes, device applications, equipment, metrology, and modeling. Contributions from a wide range of topics, from fundamental research to industrial applications and equipment are welcome.

### Contributed papers are solicited in the following areas:

- Advanced Implant/Doping and Annealing Equipment
- Annealing Technologies and Processes
- Device Applications for Implant/Doping and Annealing Processes
- Implant/Doping Technologies and Processes
- Metrologies for Implant/Doping and Annealing Processes
- Modeling and Simulation of Implant/Doping and Annealing Processes

In addition to fully contributed papers, this issue serves as the publication of record for the **International Conference on Ion Implantation Technology 2022 (IIT 2022)**.

*MRS Advances* ensures rapid dissemination to a worldwide audience of academic researchers, industry, government research institutions, and students. Editors and reviewers judge papers primarily by their scientific validity and impact within a materials community, not their perception of future significance across the entire breadth of the materials field, ensuring the materials research community has a source for the most up-to-date results impacting specific existing and emerging fields.

*MRS Advances* publishes short papers that provide a “snapshot” of an advance within the field of materials research. Such work may include important early indications from a research project that has not yet reached a conclusion, or related results that are significant but not central to the goal of the project. The scientific methods and logic should be rigorous, technically sound, and of interest to other specialists in the area of research.

### GUEST EDITOR

**Larry Larson**, Texas State University

### MANUSCRIPT SUBMISSION:

Manuscripts must be submitted via the *MRS Advances* electronic submission system by September 23, 2022. Please select “**Ion Implantation Technology 2022**” as the manuscript type. Papers will be published online once accepted. Contributed papers should target 2500 words and four figures. Invited papers can expand to 5000 words and six figures. For detailed submission information, please see [www.mrs.org/mrs-advances-manuscript-instructions/](http://www.mrs.org/mrs-advances-manuscript-instructions/)

All manuscripts will be reviewed in a normal but expedited fashion. Papers submitted by the deadline and subsequently accepted will be published in the Special Issue. Other manuscripts that are acceptable but cannot be included in the issue will be scheduled for publication in a subsequent issue of *MRS Advances*.

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Please contact [mrsadvances@mrs.org](mailto:mrsadvances@mrs.org) with any questions.

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